

IN THE CLAIMS

Please amend the claims pursuant to 37 C.F.R. § 1.121 (c) as per direction.

Please cancel Claims 6 and 7. Applicant submits a marked copy of the changes to the claims attached hereto.

Claim 1. (Currently amended) Method of manufacturing metallised substrate materials which are suitable for the manufacture of electrical circuit carriers which may be used in the gigahertz range, in which substrates having fluoropolymer surfaces are securely coated with metal layers by:

- a. pretreating the fluoropolymer surfaces with a glow discharge process in the presence of an etching gas in such a manner that the average peak-to-valley height R_a of the fluoropolymer surfaces after carrying out the pre-treatment with the glow discharge process is at the most 20 nm, averaged over $1\mu\text{m}^2$.
- b a. depositing a first metal layer containing nickel ~~being deposited~~ on the fluoropolymer surfaces by the decomposition of volatile nickel compounds by means of a glow discharge process, and
- c b. depositing a second metal layer ~~being deposited~~ on the first metal layer from a metallisation bath.

Claim 2. (Previously presented) Method according to claim 1, characterised in that the first metal layer is subsequently treated in the following process steps:

- a1. treatment of the metal layer in an atmosphere containing oxygen by means of a glow discharge process,

- a2. treatment of the metal layer in an atmosphere containing hydrogen by means of a glow discharge process.

Claim 3. (Previously presented) Method according to one of the preceding claims, characterised in that the second metal layer is deposited by means of an electroless method.

Claim 4. (Previously presented) Method according to claim 3, characterised in that a nickel layer or an alloy layer composed of nickel with boron or phosphorous is deposited as the second metal layer.

Claim 5. (Previously presented) Method according to one of the preceding claims 1 and 2, characterised in that organic nickel compounds are used as the volatile nickel compounds.

Claim 6. (Canceled)

Claim 7. (Canceled)

Claim 8. (Currently amended) Method according to one of the preceding claims 1 to 2 ~~claim 6~~, characterised in that the etching gas, during its action on the surfaces, is adjusted to a pressure of at least 20 Pa, ~~preferably at least 50 Pa~~.

Claim 9. (Currently amended) Method according to one of the preceding claims 1 to 2 ~~claim 6~~, characterised in that the fluoropolymer surfaces are pre-treated in the presence of an oxygen/tetrafluoromethane gas mixture as the etching gas.